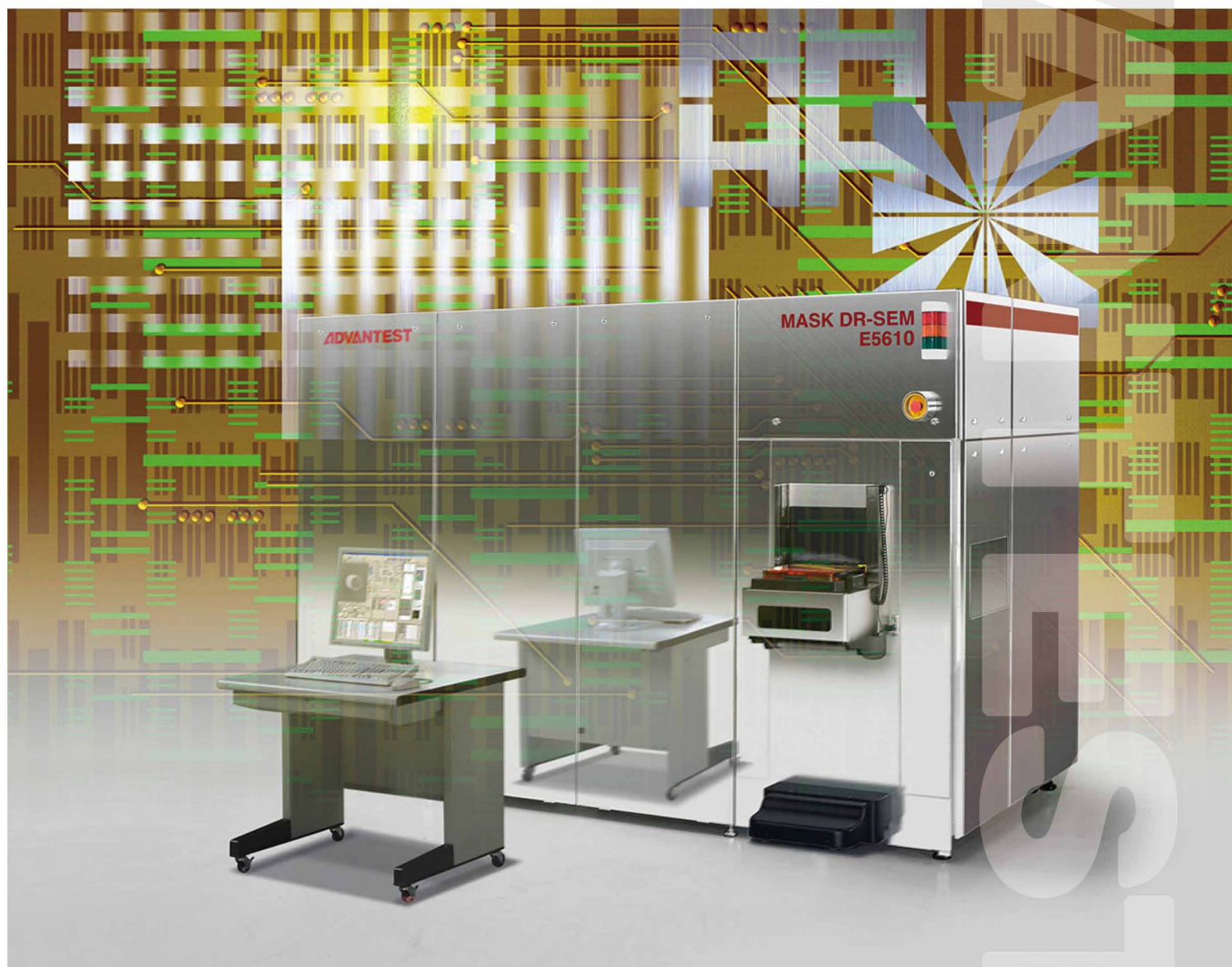


**ADVANTEST**<sup>®</sup>

**MASK DR-SEM**

# E5610

Defect Review SEM supports next-generation photomasks



The E5610 is a MASK DR-SEM<sup>1)</sup> for reviewing and classifying ultra-small defects in photomask and blanks.

Inheriting the highly stable, full automatic image capture technology developed by Advantest for its acclaimed MVM-SEM®, the E5610 easily imports defect location data from Mask Inspection System and automatically images the locations.

In addition, it features a newly developed beam tilt mechanism that enables scanning at oblique angles, and an EDS<sup>2)</sup> module that performs elemental analysis.

With its high-accuracy, high-throughput defect review capability, the E5610 is expected to contribute to next-generation photomask production quality improvement and shorter manufacturing TAT.

1) Defect Review - Scanning Electron Microscope

2) Energy Dispersive X-ray Spectrometry

## High Spatial Resolution

Advantest's proprietary column architecture delivers spatial resolution down to 2nm, even at the low acceleration voltages appropriate for photomask screening.

## High Stable, Fully Automatic Image Capture

Even when operating at high SEM magnification, the E5610 performs stable, fully automatic defect imaging at a high rate of throughput, thanks to its high-accuracy stage, charge control function, and contamination reduction technology.

## Compatible with Mask Inspection Systems

The E5610 is compatible with mainstream mask inspection systems: the tool imports defect location data and automatically images the locations identified.

## Tilt Observation Capability Option

The E5610 features a unique, electrically controlled tilt module that allows its beam to tilt by up to 15°, enabling users to perform observation of side-wall and etc.

## Elemental Composition Analysis Option

The E5610 features an EDS module that performs elemental analysis - an advanced method of mapping mask blank defects.

*MVM-SEM is either a registered trademark or a trademark of Advantest Corporation in Japan, the United States and other countries.*

## E5610 Key Specifications

<b>Supported materials:</b>	<b>6025 size photomasks</b>
<b>SEM apatial resolution:</b>	<b>2nm</b>
<b>Beam tilt degree*:</b>	<b>Maximum 15°</b>
<b>Stage position accuracy:</b>	<b>±75nm</b>
<b>Acceleration voltage:</b>	<b>0.3kV to 10kV</b>
<b>Probe current:</b>	<b>1pA to 1nA</b>
<b>EDS energy resolution*</b>	<b>138eV</b>

\*Options. Please contact us for more information regarding the tilt module and EDS module.



*Please refer to product manual for complete system specifications.*

*Specifications may change without notification.*

**ADVANTEST®**

<http://www.advantest.co.jp>

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